

### **REMARKS**

Applicant's attorney would like to thank the Examiner for the careful consideration given this case in the Office Action mailed March 23, 2006. Claims 1-20 are pending in the application. Independent Claim 1 has been amended for further clarification. Claims 10-20 have been added. Support for the claim amendments and new claims can be found in the application as originally filed. No new matter has been added.

#### **Rejection under 35 U.S.C. 102(e)**

Claims 1-9 stand rejected by the Examiner under 35 U.S.C. 102(e) as being anticipated by Chou (US Patent 5,772,905; Chou '905) or Chou (US Patent 6,309,580; Chou '580). Applicants respectfully disagree.

Initially, the Examiner's comments regarding the qualification of Chou '905 and Chou '580 as prior art under 35 U.S.C. 102(e) are noted. However, irrespective of whether the references are "by another" is immaterial for purposes of the present response. Even assuming arguendo for the purposes of this response, that these references are appropriate under 35 U.S.C. 102(e), Applicants submit that Chou '905 and Chou '580 do not anticipate the present claimed invention. The process in Chou '905 and Chou '580 is based on a different physical principle than the present claimed invention. Applicants expressly reserve the right to address the applicability of Chou '905 or Chou '580 as prior art in this or a later filed case.

As stated, Chou '905 and Chou '580 do not anticipate the present claimed invention. In particular, the claimed invention is directed to an article having a nanoscale pattern of self-assembled structures such as pillars. Chou '905 and Chou '580 do not teach or suggest this; rather, Chou '905 and Chou '580 disclose obtaining patterns by molding through pressing a

mold at high pressure into a thin film carried on the substrate to obtain holes, pillars or trenches or other patterns. Conversely, the articles of the present claimed invention have a pattern of *self assembled pillars* and other structures as such. The ultra-fine patterns of pillars are obtained by placing a mask at a constant distance from a thin film layer at the surface of a substrate and allowing self assembly of a pattern between the mask and the deformable thin film layer. The formed patterns in the present claimed invention, therefore, include pillars that are self assembled, which Chou '905 and Chou '580 do not teach or suggest. Accordingly, withdrawal of the Examiner's rejections of Claim 1 is respectfully requested.


Claims 2-9 depend directly or indirectly from and add further limitations to independent Claim 1 and are deemed allowable for at least the same reasons in connection with amended independent Claim 1. Accordingly Applicants respectfully request reconsideration and withdrawal of the Examiner's rejections of Claims 1-9.

**CONCLUSION**

It is believed that the pending claims 1-20 are in condition for allowance and notice to such effect is respectfully requested. The Commissioner is hereby authorized to charge Deposit Account No. 50-0436 for any additional fees that may be due in connection with this response.

Should the Examiner have any questions regarding this application, the Examiner is invited to initiate a telephone conference with the undersigned.

Respectfully Submitted,

  
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